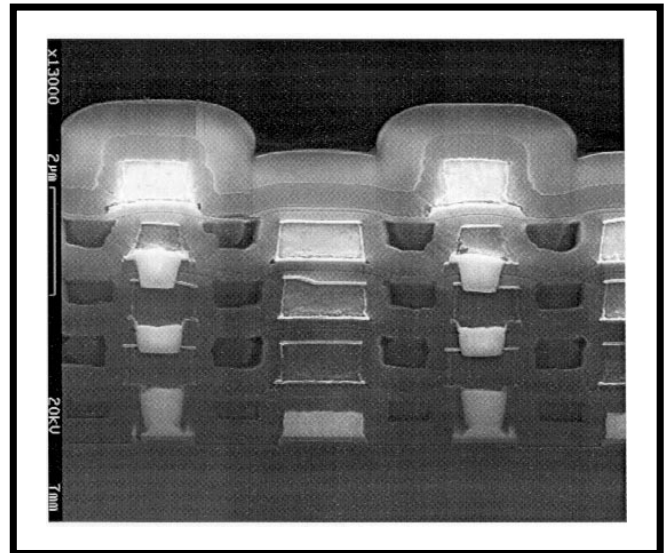


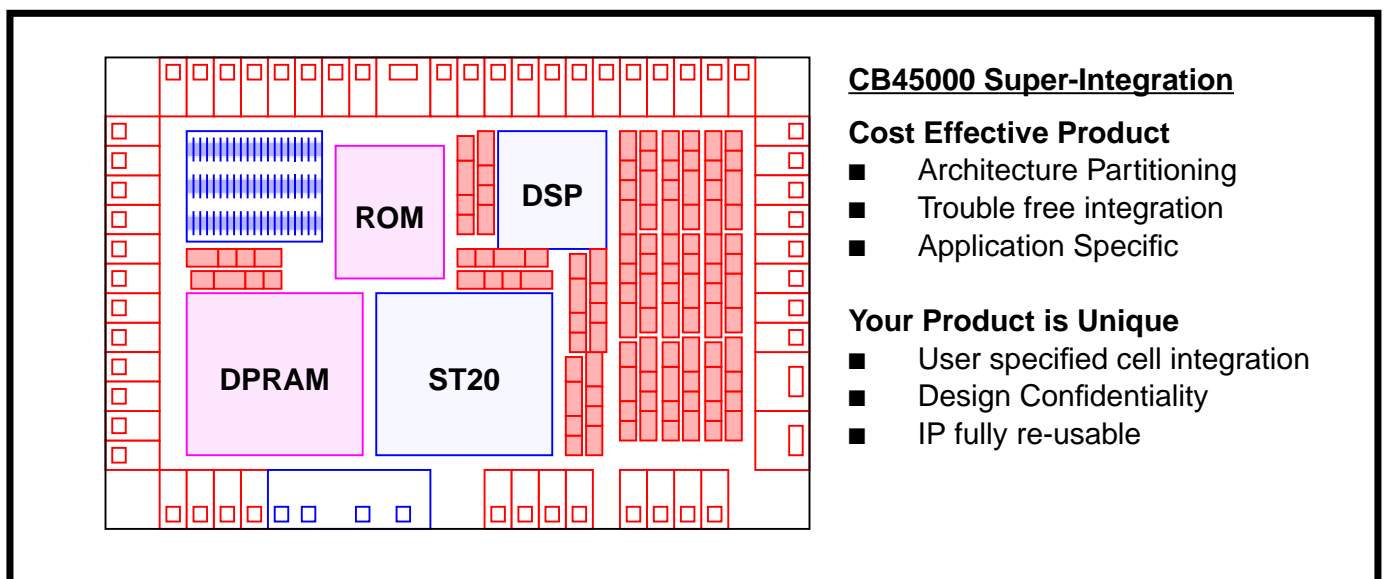
HCMOS6 STANDARD CELLS

FEATURES

- 0.35 micron 5 layer metal HCMOS6 process, retrograde well technology, low resistance salicided active areas and polysilicide gates.
- 3.3 V optimized transistor with 5 V I/O interface capability
- 2 - input NAND delay of 160 ps (typ) with fanout = 2.
- Broad I/O functionality including Low Voltage CMOS, Low Voltage TTL and LVDS. Driving capability to ISA, EISA, PCI, MCA, and SCSI interface levels
- High drive I/O; capability of sinking up to 24 mA with slew rate control, current spike suppression and impedance matching.
- Generators to support Single Port RAM, Dual Port RAM, and ROM with BIST options.
- DRAM integration in ASIC methodology
- Extensive embedded function library including ST DSP and micro cores, third party micros and Synopsys synthetic libraries.
- Fully independent power and ground configurations for inputs, core and outputs.
- I/O ring capability up to 1000 pads.
- Latchup trigger current > +/- 500 mA.
ESD protection > +/- 4000 volts typical value



- Oscillators for wide frequency spectrum.
- Broad range of 500+ SSI cells
- Design For Test features including IEEE 1149.1 JTAG Boundary Scan architecture.
- Cadence, Mentor and Synopsys based design systems with interfaces from multiple workstations.
- Broad ceramic and plastic package range.



CB45000 Super-Integration

Cost Effective Product

- Architecture Partitioning
- Trouble free integration
- Application Specific

Your Product is Unique

- User specified cell integration
- Design Confidentiality
- IP fully re-usable

CB45000 SERIES

GENERAL DESCRIPTION

The CB45000 standard cell series uses a high performance, low voltage, 5 level metal, HCMOS6 0.35 micron process to achieve sub-nanosecond internal speeds while offering very low power dissipation and high noise immunity.

With an average routed logic density of 14000 gates/mm², the CB45000 family allows the design of highly complex devices. The potential available gate count ranges above 3 Million equivalent gates. Devices can operate over a V_{dd} voltage range of 2.7 to 3.6 volts.

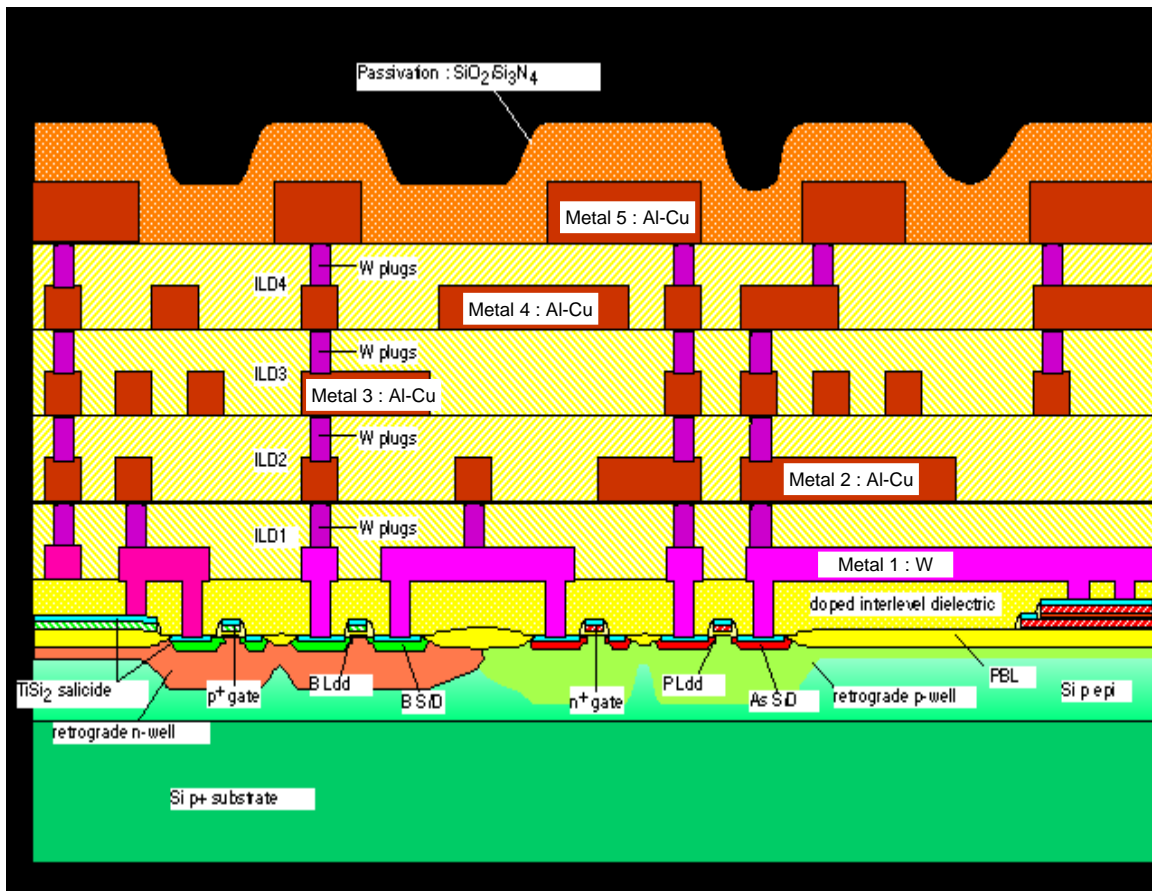
The I/O count for this array family ranges to over 750 signals and 1000 pins based upon the package technology utilized. A flexible I/O approach has been developed to provide an

optimum solution for today's complex system problems of drive levels and specialized interface standards.

The product offers a variable bonding approach supporting pad spacings from 80μ upwards and supports staggered pad rows to address today's bonding technologies. Additional flexibility to support 65μ and 50μ pad spacing will be available in the near future.

The I/O can be configured for circuits ranging from low voltage CMOS and TTL to low swing differential circuits (LVDS) and the 1Gigabit per second high speed link. Standards like SCSI, 3.3 and 5 Volt PCI and other 5.0 Volt interfaces are currently being addressed.

Figure 1
Process Overview



TECHNOLOGY OVERVIEW

A major feature of the HCMOS6 process is salicided active areas. This results in source drain areas that are on the order of one to two ohms resistance as opposed to the hundreds or thousands of ohms of source drain resistance in non-salicided technologies. This very low resistance is one reason that very low transistor widths could be utilized in the cell design since drive is not lost due to source drain resistance.

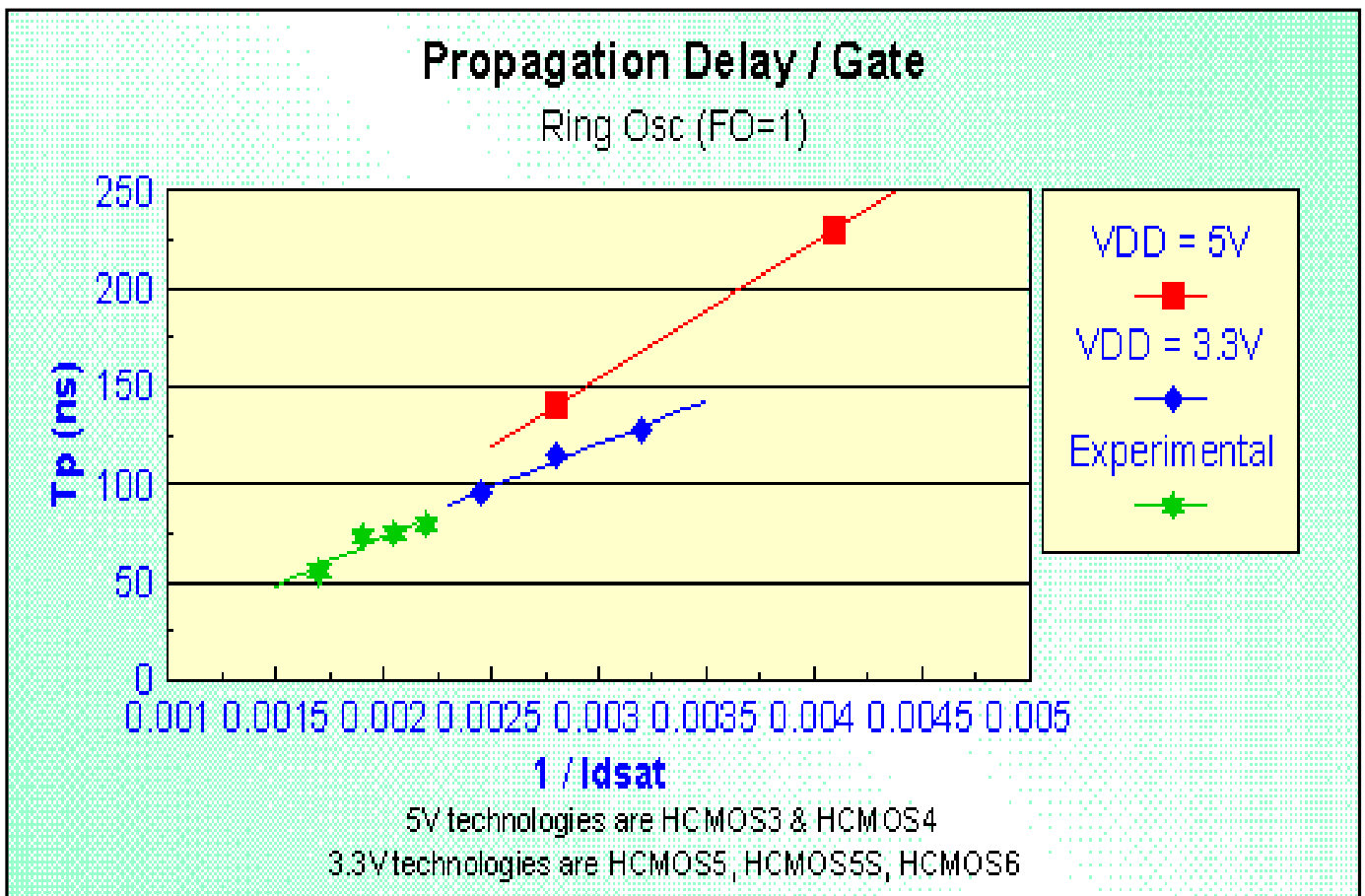
This use of low width transistors results in lower capacitance loading of the gates due to the smaller areas utilized. Low resistance, low capacitance, and small gates results in low power usage for inverters as compared to previous technologies. The reduction in power consumption allows the usage of salicided active stripes to distribute power internally to the simple cell, replacing, in some cases, the usage of the first metal layer. This saves silicon area by allowing greater density, permeability and routability of the cells resulting in greater overall circuit density.

The other major feature of the HCMOS6 process is five metal layer interconnect using CMP (Chemical Mechanical Polishing) planarization. The use of CMP for improved planarity between metal layers allows the use of additional interconnect layers without yield degradation, improving density whilst retaining low costs.

The power distribution methodology provides separate internal distributions to improve product noise margin and reduce power loss. The three supplies are:

- Internal Vdd and Vss
Serves the core cells and the prebuffer sections of the I/O
- External Vdd and Vss
Serves the output transistors only
- Receiver Vdd and Vss
Serves the first stages of the receiver cells.

Optional distributions for 5.0V interface and other standards can be utilized as necessary.



LIBRARY

The CB45000 Series library is organized into four categories:

- SSI cell library
- IO Cell library
- Macrofunctions
- Module generators

SSI CELL LIBRARY OVERVIEW

The design of the CB45000 family has been optimized to allow extremely high density, high speed and low power designs. For these reasons a wide range of cells with different ranges of driving capability are available in the library.

The library cells have been optimized in term of functional and electrical parameters in order to have:

- Good balancing
- Maximum speed
- Optimum Threshold voltage

- Symmetric Vdd/Vss Noise margin
- Minimum Power-Speed figure

The geometrical aspect of the cells was configured to allow extremely dense design, fully exploiting the features of the Place and Route tool in terms of horizontal and vertical routing grids. For Place and Route, up to five levels of metal are utilized. Intracell wiring is limited as far as possible to first metal, with second, third and fourth metal levels dedicated to interconnect wiring and power distribution. The fifth metal is used for power and clock bussing.

CORE LOGIC

The propagation delays shown in the CB45000 data book are given for nominal processing, 3.3V operation, and 25 C temperature conditions. However there are additional factors that affect the delay characteristics of the macrocells. These include loading due to fanout and interconnect routing, voltage supply, junction temperature of the device, processing tolerance and input signal transition time.

Prior to physical layout, the design system can estimate the delays associated with any critical path. The impact of the placement and routing can be accurately RC back annotated from the layout for final simulations of critical timing. The effects of junction temperature, (K_T) and voltage supply (K_V) on the delay numbers are summarized in Table 2 and Table 2. A third factor, is associated with process variation. This multiplier has a minimum of 0.8 and a maximum of 1.2.

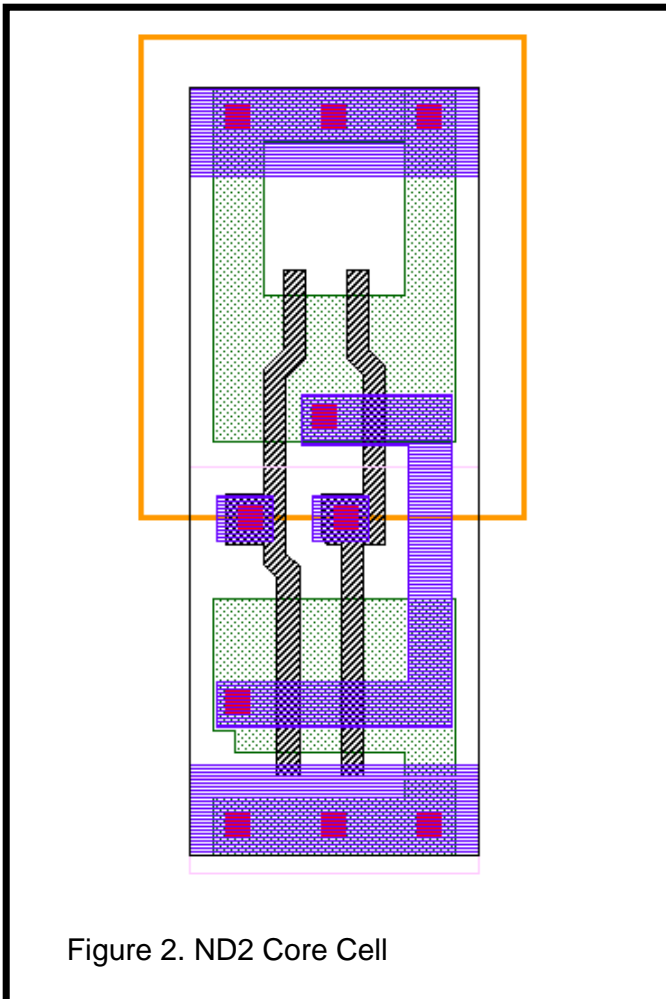


Figure 2. ND2 Core Cell

Table 1 Junction Temperature Multipliers

Temperature °C	K_T
-55	0.77
-40	0.83
25	1.00
70	1.13
85	1.17
125	1.27

Table 2 Voltage Multipliers

V _{DD}	K _V
2.7	1.20
3.0	1.11
3.3	1.00
3.6	0.94

I/O BUFFER LIBRARY

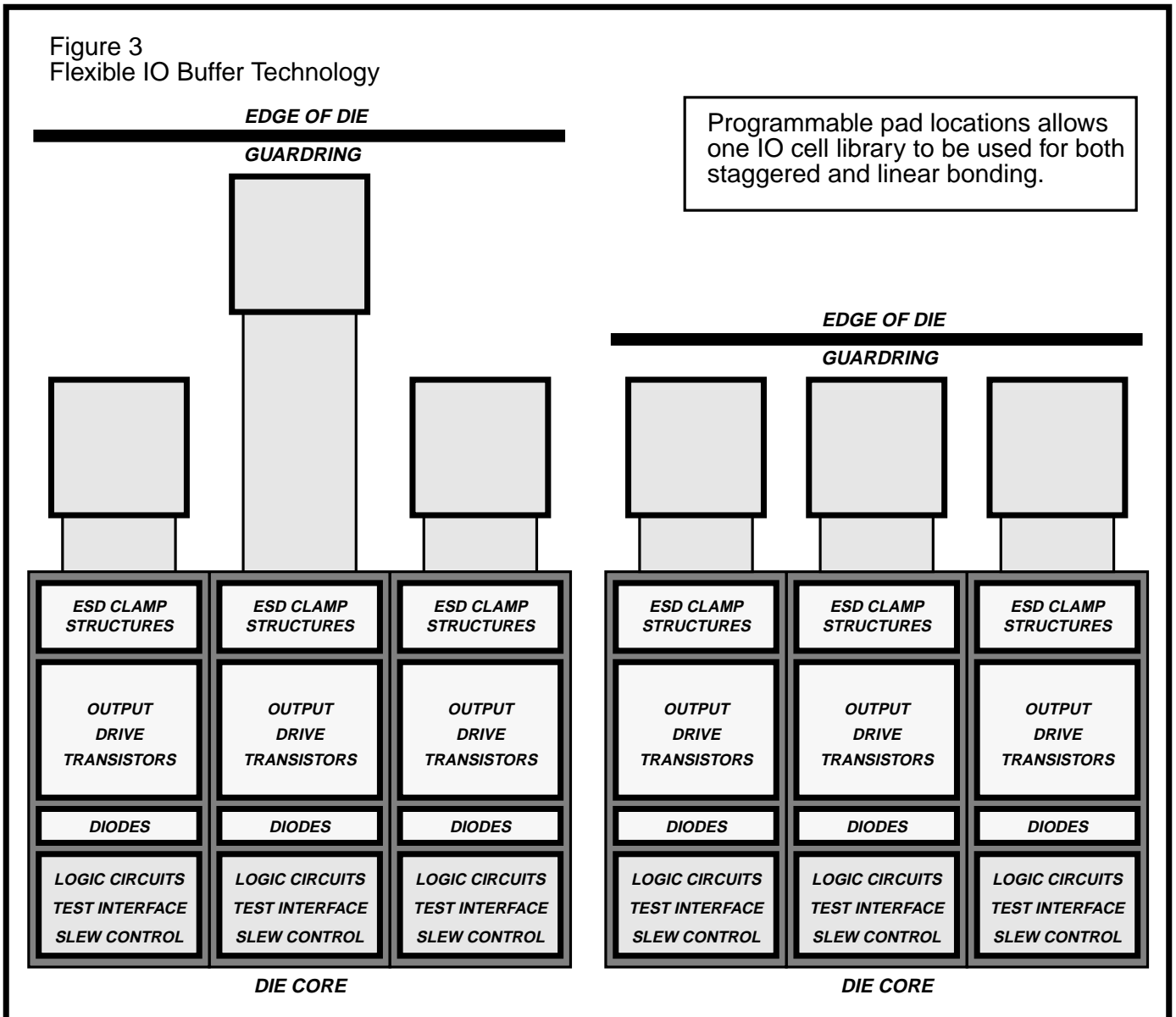
The CB45000 does not use traditional I/O cell design; SGS-THOMSON was one of the pioneers of the emerging “Flexible I/O” approach and the CB45000 features variable bonding and a flexible output transistor scheme based on a predefined

set of I/O transistor subcells.

These subcells can be quickly configured using metallization layers to conform to a variety of I/O specifications whilst maintaining optimal ESD protection levels and latch-up prevention characteristics.

The I/O circuitry also includes subcells of specialized transistors that are used to form the slew rate control sections of each I/O line. Current spike suppression logic ensures that conducting transistors are turned off before the opposing set are turned on.

The bond pad itself is variable in terms of pitch and size and even supports staggered bonding methodologies. This is becoming far more



important as the packaging options become ever broader.

The pad size and pitch are not determined until the customer's choice of packaging, signal interface standards and I/O count is considered. Wire bond pad spacings down to 65 μ and 50 μ centres will be released in the near future to support large signal counts without die area loss.

All pads except the sixteen corner pads can be configured as power or I/O pads. The configured power pads are known as placeable pads and have an associated current handling capability. Their placement is dependent on the types of output buffers used in the design. For rules governing the placement of pads, please contact your local SGS-THOMSON design centre.

Table 3 I/O Drive Capacity for LVCMOS and LVTTTL Slew Rate Buffers

Current Drive (mA)	Maximum Capacitance (pF)
2.0	50
4.0	100
8.0	200
12.0	300
16.0	400

Table 4 I/O Drive Capacity for LVCMOS and LVTTTL Non Slew Rate Buffers

Current Drive (mA)	Maximum Capacitance (pF)
2.0	50
4.0	100
8.0	200
12.0	300
16.0	400

I/O TEST INTERFACE

The IO cells have a dedicated test interface to facilitate parametric and Iddq testing of devices. This test interface connects standard core signals or dedicated test signals to the IO cells allowing all Output Buffers to be driven high, low or put into tristate regardless of the state of the internal logic.

This greatly simplifies parametric testing of the part and also assists customers who wish to use this feature during board testing. Note that all output buffers can be tristated by this function including buffers that normally do not tristate.

This test function also turns off all pull up or down devices and shuts down all differential receivers and converts them into standard CMOS receivers. This allows Iddq test methodologies to be employed in a very efficient way, avoiding unneeded circuit overhead.

Inside the IO cell is a section of specialized transistors used to create the receiver functions. A full set of standard receivers with pull up and pull down devices is present in the library. The technologies supported match the output buffer capabilities and include, LVCMOS, LVTTTL, GTL, CTL, Differential, etc. and a five volt interface capability.

MACROCELLS AND MACROFUNCTIONS

The CB45000 series has internal macrocells that are robust in variety and performance. The cell selection has been driven by the need of Synthesis and HDL based design techniques. This offering is rich in buffers, complex combinatorial cells and multi power drive cells, which allow the Synthesis tool to create a netlist compatible with the requirements of Place and Route tools.

Macrofunctions are a series of soft-macros facilitating quick capture of large functional blocks and are available for such functions as counters, shift register and adders. Macrofunctions are implemented at layout by utilizing macrocells and interconnecting to create the logic function.

Table 5 Module Generator Library

Cell	Description
SPRAM	256K bits max 16K word max 128 bit max Zero static current, Tristate outputs
DPRAM	256K bits max 16K word max 128 bit max Zero static current, Tristate outputs
ROM	2M bits max 32K word max 64 bit max Diffusion programmable, Tristate outputs

MODULE GENERATORS

A series of module generators using compiled cell generation techniques, are available to support a range of megacells. These modules enable the designer to choose individual parameters in order to create a compiled cell, which meets the specific application requirements. These include single port RAM, dual port RAM and ROM.

The compiled cell generators construct custom cells, which are implemented using a special leaf cell technique, ensuring predictable layout and accurate module characteristics. In choosing megacells the designer can consider the trade-offs between speed and area to generate a fully customized cell which meets their specific device requirements.

MEGACELLS

These megacell generators are complemented by a group of application specific embedded megacells. These allow access to technologies that have been hitherto the domain of standard products. Examples include mixed mode cells for graphics, DAC/ADC's (4-9 bit), PLL applications, and Digital Signal Processor functions for cellular comms, fax and high-speed modems, which initially consist of a Triple 8-bit DAC, Graphics RAM, Clock Multiplier PLL and Frequency Synthesis PLL.

100 Mbps serial transputer links coupled with large and fast memory can be used for pipelining,

caching and synchro circuits in modern RISC computing architectures. Viterbi and Reed Solomon cores aim at the HDTV and satellite transmission markets. To support telecom needs for CCITT standard applications, ADPCM cells supporting CT2 protocol have been developed.

DESIGN FOR TESTABILITY

The time and cost for ASIC testing increases exponentially as the complexity and size of the ASIC grows. Using a design for testability methodology allows large, more complex ASICs to be efficiently and economically tested.

CB45000 supports the JTAG boundary Scan and both edge and level sensitive scan design techniques by providing the necessary macrocells. Scan testing aids device testability by permitting access to internal nodes without requiring a separate external connection for each node accessed. Testability is assured at device level with the close coupling of LSSD latch elements, Automatic Test Pattern Generation (ATPG) and high pattern depth tester architecture. BIST options for memory generators are also available.

At system level, SGS-THOMSON fully supports IEEE 1149.1, and the I/O structure utilized in this family is completely compatible. Several types of core scan cells are provided in the CB45000 Series library. Examples include FDxS/FJKxS cells which are edge sensitive and LSxx cells

CB45000 SERIES

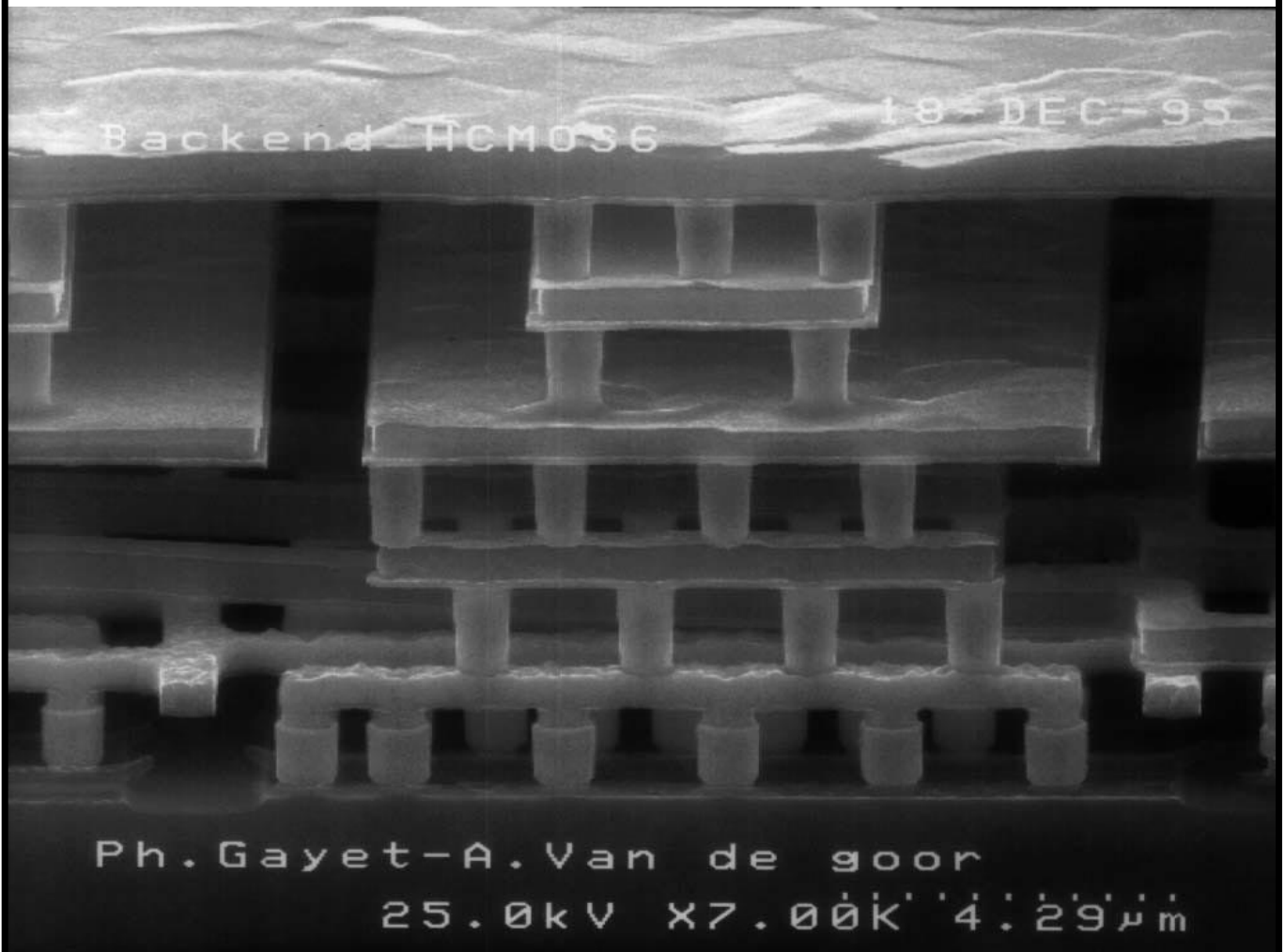
which are true LSSD cells. Non-overlapping clock generator macros are also available.

For parametric and Iddq testing, the I/O cells contain a dedicated test interface as described previously (See "I/O TEST INTERFACE" on page 6.)

EVALUATION DEVICE

An evaluation device is used to demonstrate the performance of the CB45000 series as well as verify the effectiveness of the design system. The device has path delays, latches and a set of macrocells and memory functions which were used to verify the simulated characteristics that are supplied in the data book. Characterization of the path delays including interconnect shows typical delays of 160 ps for a 2 input NAND with receivers/drivers operating at frequencies of 200 MHz. The evaluation device is available in a 208 pin plastic quad flat pack.

Figure 5
Evaluation Device Cross Section



PACKAGE AVAILABILITY

The CB45000 Series is designed to be compatible with QFP, BGA and SBC package types, in addition to the more traditional types found.

The options include Plastic Leaded Chip Carriers (PLCC) up to 84 pins, while the Metric Quad Flat Pack (xQFP) offering ranges up to 208 pins. Both high performance and high power variants are available as well as the TQFP thin types.

Ball Grid Array (BGA) packages are available from 160 to 500 pins with further developments planned in the near future. SBC types allow the pin count to reach the area of 1000 pins.

The diversity in pin count and package style gives the designer the opportunity to find the best compromise for system size, cost and performance requirements.

Figure 6
Packaging Capability

NUMBER OF LEADS (Pins)	PACKAGE NAME				
	PQFP	TQFP	BGA	PLCC	POWER PQFP Slug/Spreader
20				○	
28				○	
44	○			○	
64	○	○			
68				○	
80	○	○			
84				○	
100	○	○			
120	○				○
128	○				○
144	○	○			○
160	○				○
176		○			
180					
208	○				○
224					
225			○		
256			○		
257					
304					
352			★		
400			★		
480			★		

- Packages in Production
- ★ Packages in Development

Figure 8
SGS-THOMSON Layout Driven Design Flow

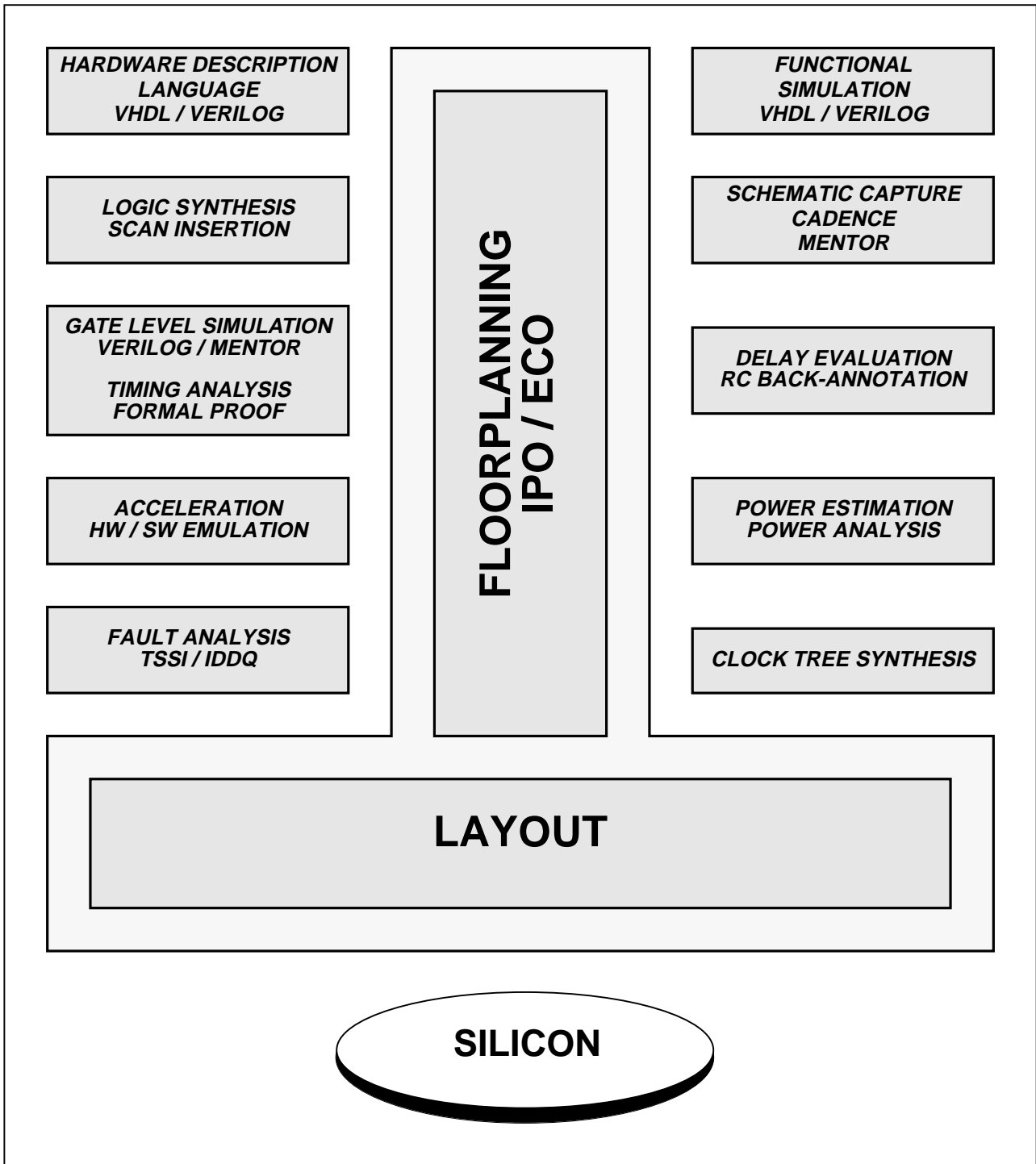


Table 6 Absolute Maximum Ratings (note1)

Supply Voltage, Vdd	-0.5 V to + 4.6 V
Input or Output Voltage	-0.5 V to (Vdd + 0.5V)
5 Volt Tolerant Input or Output Voltage	-0.5 V to +6.0 V
DC Forward Bias Current, Input or Output	-24mA source, +24mA sink
Storage Temperature Ceramic	-65 to 150 degrees Centigrade
Storage Temperature Plastic	-40 to 125 degrees Centigrade

Note 1. Referenced to Vss. Stresses above those listed under "absolute Maximum Ratings" may cause permanent damage to the device. This is a stress rating only and functional operation of the device at these or any other conditions above those indicated in the operation sections of this specification is not implied. Exposure to absolute maximum rating conditions for extended periods may affect the device reliability.

Note 2. A dedicated 5V extra power supply is needed in case of PCI buffer usage in order to clip the incoming signal on PCI pads to the 5 Volt tolerant specified Absolute Maximum Rating (5V + Vbe value)R.

Table 7 Recommended DC Operating Conditions

Normal Operating Supply Voltage Vdd (note 1)	3.3 V +/- 10% (3.0 V to 3.6 V)
Extended Operating Supply Voltage Vdd (notes 1,2)	3.3 V + 0.3V/-0.6V (2.7V to 3.6V)
Operating Ambient Temperature	
Commercial (note 3)	0 to 70 degrees Centigrade
Industrial (note 3)	-40 to +85 degrees Centigrade
Military (note 4)	-55 to +125 degrees Centigrade

Note 1. Commercial, Industrial, and Military Conditions

Note 2. Low Voltage TTL Circuits are NOT functional to specifications below 3.0 Volts

Note 3. All circuits will operate to full specifications with a Vdd of 3.0V to 3.6V and a junction temperature of -40 to +125 degrees centigrade. These junction temperatures are compatible with the Commercial and Industrial Temperature Ranges.

Note 4. All circuits will be functional from -55 to +150 degrees centigrade junction temperature (military Ambient Temperature Range) but will not necessary operate to published specifications. Only circuits specified as operational to extended temperature range may be used when operating to Military temperature conditions.

Table 8 General Interface DC Electrical Characteristics (Note 1)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Iil	Low Level Input Current	Vi = Vss			+/-10	uA	2
Iih	High Level Input Current	Vi = Vdd			+/-10	uA	2
Ioz	Tri-State Output Leakage	Vo=0V or Vdd			+/-10	uA	2
Cin	Input Capacitance	Freq=1MHz		2.5	4.0	pF	3,4
Co	Output Capacitance	Freq=1MHz		4.0	5.5	pF	3,4
Cio	Bidi, I/O Capacitance	Freq=1MHz		5..0	6.5	pF	3,4
Iklu	I/O Latch Up Current	V<Vss, V>Vdd	200	500		mA	
Vesd	Electrostatic Protection	HBM	2000			V	5

Note 1. These are extended voltage and temperature specifications
Vdd from 2.7 V to 3.6 V ; Temperature Ambient from -55 to 125 degrees Centigrade

Note 2. Adherence to rules in Power Pin / Pad Specifications Required

Note 3. Excluding Package

Note 4. At 0.0 Volts

Note 5. Human Body Model

Table 9 LVTTTL Interface DC Electrical Characteristics (Note 1)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Vil	Low Level Input Voltage				0.8	Volts	2,3
Vih	High Level Input Voltage		2.0			Volts	2,3
Vol	Low Level Output Voltage	Iol = Rated Buffer Current		0.2	0.4	Volts	2,3,4
Voh	High Level Output Voltage	Ioh = Rated Buffer Current	2.4	3.0		Volts	2,3,4
Vt +	Schmitt Trigger +Ve Threshold			1.7	1.9	Volts	2,3
Vt -	Schmitt Trigger -Ve Threshold		0.9	1.1		Volts	2,3

Note 1. These are normal Voltage and extended temperature specifications
Vdd from 3.0 V to 3.6 V

Temperature Ambient from -55 to 125 degrees Centigrade

Note 2. Adherence to rules in Power Pin / Pad Specifications Required

Note 3. Refer to the CB45000 Standard Cell Specification for full Testing Levels and Conditions

Note 4. Buffers offered in 2, 4, 8 mA TTL options (12, 16 and 24 mA available on request)

Table 10 LVCMOS Interface DC Electrical Characteristics (Note 1)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Vil	Low Level Input Voltage				0.2xVdd	Volts	2,3,4
Vih	High Level Input Voltage		0.8 x Vdd			Volts	2,3,4
Vol	Low Level Output Voltage	Iol = Rated Buffer Current		0.2	0.4	Volts	2,3,4,5,6
Voh	High Level Output Voltage	Ioh = Rated Buffer Current	0.85 x Vdd	0.9 x Vdd		Volts	2,3,4,5,6
Vt +	Schmitt Trigger +Ve Threshold			1.7	1.9	Volts	2,3
Vt -	Schmitt Trigger -Ve Threshold		0.9	1.1		Volts	2,3

Note 1. These are extended voltage and temperature specifications
Vdd from 2.7 V to 3.6 V

Temperature Ambient from -55 to 125 degrees Centigrade

Note 2. Adherence to rules in Power Pin / Pad Specifications Required

Note 3. Refer to the CB45000 Standard Cell Specification for full Testing Levels and Conditions

Note 4. Buffers offered in 2, 4, and 8 mA CMOS options

Note 5. Note only one CMOS buffer may sink or source DC current when parametric measurements are taken due to the reason that the power supply specifications for CMOS product are not written to support DC current. If more than one buffer is active voltage drops in the supply may cause false failure readings.

Note 6. If no buffers are sinking or sourcing current and all internal pull up or pull down resistors in bidi buffers have been disabled by having the T2 Test Pin positive Vol (max) = 0.05 Volts and Voh (min)=Vdd-0.05 Volts

CB45000 SERIES

Table 11 Five Volt Tolerant Interface DC Electrical Characteristics (Note 1,2)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Vil	Low Level Input Voltage				0.8	Volts	3,4
Vih	High Level Input Voltage		2.0			Volts	3,4
Vol	Low Level Output Voltage	Iol = Rated Buffer Current		0.2	0.4	Volts	3,4,5
Voh	High Level Output Voltage	Ioh = Rated Buffer Current	2.4	3.0		Volts	3,4,5
Vt +	Schmitt Trigger +Ve Threshold			1.7	1.9	Volts	3,4
Vt -	Schmitt Trigger -Ve Threshold		0.9	1.1		Volts	3,4

Note 1. Five Volt Tolerant Inputs: receivers allowed to receive a 5V signal while being supplied at 3.3V
Five Volt Tolerant Output: drivers allowed to drive external loads between 0V and 3.3V while being supplied at 3.3V having the ability to sustain 5V signals when tristated.

Note 2. These are normal Voltage and extended temperature specifications
TTL specification only; Vdd from 3.0 V to 3.6 V
Temperature Ambient from -55 to 125 degrees Centigrade

Note 3. Adherence to rules in Power Pin / Pad Specifications Required

Note 4. Refer to the CB45000 Standard Cell Specification for full Testing Levels and Conditions

Note 5. Buffers offered in 3, 4, 6, 8 mA TTL options

DESIGN CENTRES

USA

Carrollton, TX 75006-5039

1310 Electronics Drive
MS 2337
Tel.: (1) 972/466-8844

Lincoln, MA 01773

55 Old Bedford Rd.
Tel.: (1) 617/258-0300

San Jose, CA 95110

2055 Gateway Place
Suite 300
Tel.: (1) 408/452-8585

EUROPE

FRANCE

94253 Gentilly Cedex
7, avenue Gallieni - BP 93
Tel.: (33-1) 47407575

GERMANY

8011 Grasbrunn
Bretonischer Ring 4
Neukeferloh Technopark
Tel.: (49-89) 460060

ITALY

20090 Assago (MI)
Viale Milanofiori
Strade 4 - Palazzo A/4/A
Tel.: (39-2) 89213215

40033 Casalecchio di Reno (BO)
Via R. Fucini, 12
Tel.: (39-51) 591914

SWEDEN

S-16421 Kista
Borgarfjordsgatan, 13
Box 1094
Tel.: (46-8) 7939220

UNITED KINGDOM and EIRE

Marlow, Bucks SL7 1YL
Planar House, Parkway
Globe Park
Tel.: (44-1628) 890800

ASIA/PACIFIC

HONG KONG

Wanchai
22nd Floor
Hopewell Centre
183 Queen's Road East
Tel.: (852-5) 8615788

KOREA

Seoul 121
8th floor Shinwon Building
823-14, Kuksman-Dong
Kang-Nam-Gu
Tel.: (82-2) 553-0399

SINGAPORE

Singapore 2056
28 Ang Mo Kio
Industrial Park 2
Tel.: (65) 482-1411

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